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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/674,647	09/30/2003	Kwang Su Choe	YOR920030293US1 (16818)	4796
Steven Fischm	7590 12/04/200 ran ESO	EXAM	EXAMINER	
Scully, Scott, I	Murphy and Presser	PADGETT, MARIANNE L		
400 Garden Ci Garden City, N			ART UNIT	PAPER NUMBER
,,,-			1792	
			MAIL DATE	DELIVERY MODE
			12/04/2008	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Advisory Action Before the Filing of an Appeal Brief

Application No.	Applicant(s)	
10/674,647	CHOE ET AL.	
Examiner	Art Unit	
MARIANNE L. PADGETT	1792	

	MARIANNE L. PADGETT	1792				
The MAILING DATE of this communication appe	ars on the cover sheet with the o	correspondence add	ress			
THE REPLY FILED 24 November 2008 FAILS TO PLACE THIS	APPLICATION IN CONDITION F	OR ALLOWANCE.				
☑ The reply was filed after a final rejection, but prior to or on the same day as filing a Notice of Appeal. To avoid abandonment of thi application, applicant must timely file one of the following replies: (1) an amendment, affidavt, or other evidence, which places the application in condition for allowance; (2) a Notice of Appeal (with appeal fee) in compliance with 37 CFR 41.31; or (3) a Request for Continued Examination (RCE) in compliance with 37 CFR 1.114. The reply must be filed within one of the following time periods:						
 a) The period for reply expiresmonths from the mailing 	date of the final rejection.					
no event, however, will the statutory period for reply expire to	The period for reply expires on: (1) the mailing date of this Advisory Action, or (2) the date set forth in the final rejection, whichever is later. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of the final rejection. Examiner Note: If box 1 is checked, checke lither box (a) or (b), ONLY CHECK BOX (b) WHEN THE FIRST REPLY WAS FILED WITHIN TWO.					
MONTHS OF THE FINAL REJECTION. See MPEP 706.07().					
Extensions of time may be obtained under 37 CFR 1.136(a). The date have been filled is the date for purposes of determining the period of extended under 37 CFR 1.17(a) is calculated from: (1) the expiration date of the set forth in (b) above, if Checked, Any reply received by the Office later may reduce any earned patent term adjustment. See 37 CFR 1.704(b).	ension and the corresponding amount of hortened statutory period for reply origing than three months after the mailing date	of the fee. The appropria inally set in the final Office	ate extension fee te action; or (2) as			
NOTICE OF APPEAL	F '41 07 OFD 44 07	Filed Mile to the comments				
 The Notice of Appeal was filed on A brief in comp filing the Notice of Appeal (37 CFR 41.37(a)), or any exter Notice of Appeal has been filed, any reply must be filed w 	sion thereof (37 CFR 41.37(e)), to	avoid dismissal of the	s of the date of appeal. Since			
AMENDMENTS						
 ∑ The proposed amendment(s) filed after a final rejection, to (a) ∑ They raise new issues that would require further core. (b) ∑ They raise the issue of new matter (see NOTE below) (c) ☐ They are not deemed to place the application in bet 	nsideration and/or search (see NOT w);	TE below);				
(c) in they are not deemed to place the application in bet appeal; and/or	ter form for appeal by materially rec	auding or simplifying ti	ne issues for			
(d) They present additional claims without canceling a	corresponding number of finally reje	cted claims.				
NOTE: See Continuation Sheet. (See 37 CFR 1.1						
 The amendments are not in compliance with 37 CFR 1.12 		mpliant Amendment (I	PTOL-324).			
 Applicant's reply has overcome the following rejection(s): 						
Newly proposed or amended claim(s) would be all non-allowable claim(s).		•				
 For purposes of appeal, the proposed amendment(s): a) how the new or amended claims would be rejected is provided to the proposed amendment of the proposed amend		i be entered and an ex	xplanation of			
The status of the claim(s) is (or will be) as follows: Claim(s) allowed:						
Claim(s) objected to:						
Claim(s) rejected: <u>1-11 and 13-25</u> .						
Claim(s) withdrawn from consideration: AFFIDAVIT OR OTHER EVIDENCE						
8. The affidavit or other evidence filed after a final action, bu	t before or on the date of filing a No	otice of Anneal will not	he entered			
because applicant failed to provide a showing of good and was not earlier presented. See 37 CFR 1.116(e).						
 The affidavit or other evidence filed after the date of filing entered because the affidavit or other evidence failed to o showing a good and sufficient reasons why it is necessary 	vercome <u>all</u> rejections under appea	al and/or appellant fail:	s to provide a			
10. The affidavit or other evidence is entered. An explanation REQUEST FOR RECONSIDERATION/OTHER	n of the status of the claims after er	ntry is below or attach	ed.			
The request for reconsideration has been considered bu See Continuation Sheet.	does NOT place the application in	condition for allowan	ce because:			
12. Note the attached Information Disclosure Statement(s). (PTO/SB/08) Paper No(s).						
13. Other:						
	/Marianna L Dad#/					
	/Marianne L. Padgett/ Primary Examiner, Art U	nit 1792				

Continuation of 3 NOTE:

- (1) The blanket implantation of oxygen ions to a uniform depth is a new issue, in that white blanket implantation was previously considered (claim 14), "uniform depth" was not a not according to uniform depth was found in the original specification. The hand drawn cross-sectional illustration of the layered substrata figure 2C, cannot be considered to provide details or support or definition for uniform thickness. Furthermore, in paragraph (00/21 applicants have defined "uniform" for the entire specified not always mean "a buried oxide region have been a continuous interface with a S-containing over layer as well as the underlying S-containing substrate wherein the variation of thickness across the entire surface is less than 30% of the total thickness of the buried oxide layer", thus prohibiting any clear meaning for "uniform" when used in combination with "depth" of oxygen ion implantation. Thus, the "uniform depth" amendments in the independent claims & paragraph [0037] rised question of new matter, as well as being new issues.
- (2) The amendment to paragraph [0048] raises the issue of whether or not this amendment broadens the scope of the original disclosure, thus introducing new matter, by broadening the disclosure of the embodiment from removing excess dopant hat were ion implanted, to generic removal of excess dopant species no matter where they came from.
- (3) The effect of a sequential annealing step in hydrogen reducing dopant levels within the SOI structure is a new issue in that it has not been previously claimed, thus required to be examined with respect to prior art. Note this also requires consideration with respect to the broadened disciosure of [0048].

Continuation of 5. Applicant's reply has overcome the following rejection(s):

Aside from above new issue/new matter considerations, the proposed amendment appear to remove first & second paragraph rejections of sections 1 & 3 of the action mailed 10/1/08.

Continuation of 11. does NOT place the application in condition for allowance because:

Above new issues require further consideration, for example, it must be considered what is meant by "uniform depth", which is present neither in original claim 14, nor in [0037], and could mean all ions are implanted to be approximately same depth, or a range of depths is approximately the same where implantation occurs, etc., and further what scale uniform is to be considered on (microscopic, macroscopic, etc.) as not known.

With respect to the prior art, Bendernagel et al. (518), while teaching masking as one embodiment that may be employed with the ion implantation of oxygen, does not require that masking or patterning necessarily be employed, specifically noting in column 9, lines 62-64, pointed out by applicants, that "... ion implantation process wherein ions are implanted only into predetermined areas...", which encompasses selection of an entire surface area, selectively deposited to a desired depth, such as in their claim (10) "ions into predetermined areas... implant regions at or near said interface", which may be considered to read on possible meanings of uniform depth. Attenatively, if one considers predetermined area not to necessarily encompass blanks timplantation, it must be further considered whether or not discontinuous patterning versus blanks timplantation is an obvious difference, or has some unexpected or unobvious significance, which is not appearent from equivalently supplied laternative options of blanks t a pattern of [0037]. Also, its noted Bendermagel et al. in column 9, lines 40-50, teach hydrogen annealing from the claimed purpose & after oxygen annealing, thus while this amendment to the hydrogen annealing fixes 112 (susses, it is a limitation covered by this reference).

/MLP/ 12/1-2/2008